

# EUROPEAN PATENT OFFICE

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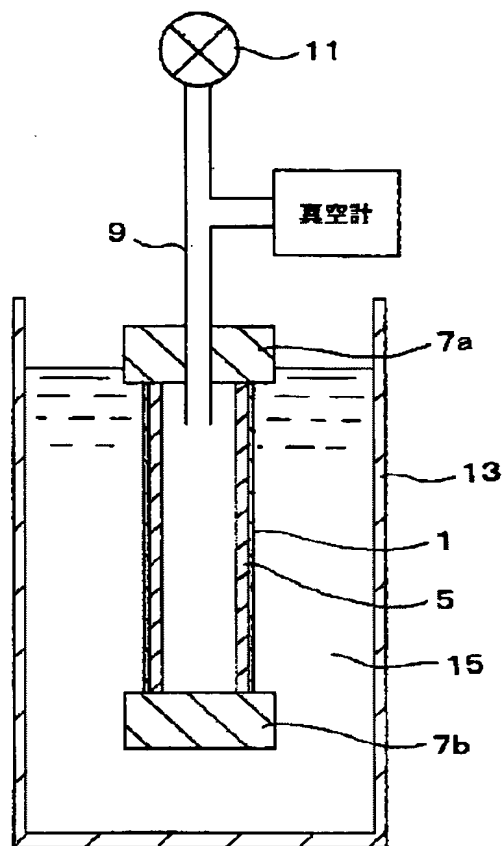
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TITLE : DEFECT RESTORING METHOD OF  
MEMBRANE FORMED ON POROUS  
SUBSTRATE, MEMBRANE  
SEPARATING BODY AND GAS  
SEPARATING BODY WITH DEFECT OF  
MEMBRANE RESTORED



ABSTRACT : PROBLEM TO BE SOLVED: To provide a method for easily restoring defects caused in a membrane formed on a porous substrate without much trouble and long time, and provide a membrane separating body and a gas separating body in which the defects of the membrane are restored by the same.

SOLUTION: This method restores the defects caused in the membrane 1 formed on the porous substrate 5. The surface of the membrane 1 is immersed in solution 15 containing a binder component to solidify the surface of the membrane 1 through drying, and the solution 15 is flowed in the surface of the porous substrate 5 at the lower part of the defect area from the defect area of the membrane 1 by the vacuuming at the rear side of the porous substrate 5. The binder component in the solution 15 is solidified in the surface layer of the porous substrate 5 by reduction of flow rate due to increase in pressure loss on the surface of the porous substrate 5 and by increase in viscosity due to drying accompanied by the vacuuming, and only the porous substrate 5 at the lower part of the defect area is airtightened and the defect area is filled up.

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